

## CLAIMS

1. A chemical amplification type positive resist composition comprising a resin having a butyrolactone residue which may be optionally substituted with an alkyl and a group  
5 capable of cleaving by an action of an acid, and an acid generator.

2. The composition according to claim 1, wherein the resin has an alicyclic ring, in addition to the butyrolactone residue and the group capable of cleaving the action of the acid.

3. The composition according to claim 1, wherein the  
10 butyrolactone residue is linked to the resin base via an ester or ether linkage.

4. The composition according to claim 1, wherein the butyrolactone residue is an  $\alpha$ -residue of butyrolactone.

5. The composition according to claim 1, wherein the group  
15 capable of cleaving the action of the acid has an alicyclic ring.